

AMENDMENTS TO THE CLAIMS

1-5. (Cancelled)

6. (New) A method for manufacturing a plasma display panel (PDP) including a process for forming a metal oxide film onto a substrate of the PDP, the method comprising:

forming the metal oxide film in a deposition room having a degree of vacuum within a range of 1×10^{-1} Pa to 1×10^{-2} Pa; and

maintaining the degree of vacuum by

introducing at least one gas selected from the group consisting of oxygen, water, hydrogen, carbon monoxide, carbon dioxide and inert gas into the deposition room, and

controlling and equilibrating an amount of gas introduced into the deposition room and an amount of gas exhausted from the deposition room.

7. (New) The method for manufacturing the PDP of claim 6, wherein the at least one gas includes oxygen, and wherein said maintaining of the degree of vacuum further comprises:

introducing at least one gas selected from the group consisting of water, hydrogen, carbon monoxide and carbon dioxide at a constant amount into the deposition room; and

adjusting an amount of the oxygen gas introduced into the deposition room.

8. (New) The method for manufacturing the PDP of claim 6, wherein said introducing of at least one gas comprises introducing at least one gas selected from the group consisting of water, hydrogen, carbon monoxide and carbon dioxide, and wherein said maintaining of the degree of vacuum further comprises:

introducing an amount of oxygen at a constant value; and

adjusting an amount of the at least one gas selected from the group consisting of water, hydrogen, carbon monoxide and carbon dioxide introduced into the deposition room.

9. (New) The method for manufacturing the PDP of claim 6, wherein the at least one gas includes inert gas, and wherein said maintaining of the degree of vacuum further comprises:

introducing at least one gas selected from the group consisting of oxygen, water, hydrogen, carbon monoxide and carbon dioxide at a constant value into the deposition room; and adjusting an amount of the inert gas introduced into the deposition room.

10. (New) The method for manufacturing the PDP of claim 6, wherein said introducing of at least one gas comprises introducing oxygen gas and at least one gas selected from the group consisting of carbon dioxide and inert gas, and wherein said maintaining of the degree of vacuum further comprises:

adjusting an amount of the oxygen gas and the at least one gas selected from the group consisting of carbon dioxide and inert gas introduced into the deposition room.